REFERENCES

[1] J.V. den B. Jan Haisma, Martin Verheijen, Kees van den Heuvel, J. Vac. Sci. Technol. B Microelectron. Nanom. Struct. **14**, (1996) 4124.

[2] A.M. Yasuhiko Tada, Hiroshi Yoshida, J. Photopolym. Sci. Technol. **4**, (2007) 545.

[3] D. Truffier-Boutry, M. Zelsmann, J. De Girolamo, J. Boussey, C. Lombard, B. Pépin-Donat, Appl. Phys. Lett. **94**, (2009) 044110.

[4] J. Takahashi, J. Taniguchi, Microelectron. Eng. **88**, (2011) 2141.

[5] J. Taniguchi, K. Machinaga, N. Unno, N. Sakai, Microelectron. Eng. **86**, (2009) 676.

[6] A. Mayer, K. Dhima, S. Möllenbeck, S. Wang, H.-C. Scheer, J. Sakamoto, H. Kawata, Y. Hirai, J. Vac. Sci. Technol. B Microelectron. Nanom. Struct. **30**, (2012) 06FB03.

[7] N. Bogdanski, M. Wissen, S. Möllenbeck, H.-C. Scheer, J. Vac. Sci. Technol. B Microelectron. Nanom. Struct. **24**, (2006) 2998.

[8] M. Otto, M. Bender, B. Hadam, B. Spangenberg, H. Kurz, Microelectron. Eng. **57**, (2001) 361.

[9] L.. Heyderman, H. Schift, C. David, J. Gobrecht, T. Schweizer, Microelectron. Eng. **54**, (2000) 229.

[10] R.N. Wenzel, Ind. Eng. Chem. **28**, (1936) 988.

[11] A.B.D.Cassie, S. Baxter, Trans. Faraday Soc. **40**, (1944) 546.

[12] E.E. Miller, R.D. Miller, J. Appl. Phys. **27**, (1956) 324.

[13] K. Osari, N. Unno, J. Taniguchi, K. Machinaga, T. Ohsaki, N. Sakai, Microelectron. Eng. **87**, (2010) 918.

[14] K. Machinaga, J. Taniguchi, N. Unno, N. Sakai, T. Ohsaki, Seikei-Kakou **21**, (2010) 346 [in Japanese].

[15] N. Unno, K. Osari, K. Machinaga, J. Taniguchi, T. Ohsaki, N. Sakai, J. Photopolym. Sci. Technol. **22**, (2009) 161.

[16] A. del Campo, E. Arzt, Chem. Rev. **108**, (2008) 911.

[17] W.K. Neo, M.B. Chan-Park, Macromol. Rapid Commun. **26**, (2005) 1008.

[18] J. Taniguchi, Y. Nemoto, Y. Sugiyama, J. Nanosci. Nanotechnol. **9**, (2009) 445.

[19] N.B. Abu Talip[a]Yusof, J. Taniguchi, Microelectron. Eng. **110**, (2013) 163.

[20] D. Truffier-Boutry, a. Beaurain, R. Galand, B. Pelissier, J. Boussey, M. Zelsmann, Microelectron. Eng. **87**, (2010) 122.

[21] J. Taniguchi, Y. Kamiya, T. Ohsaki, N. Sakai, J. Photopolym. Sci. Technol. **22**, (2009) 175.

[22] J. Taniguchi, Y. Kamiya, T. Ohsaki, N. Sakai, Microelectron. Eng. **87**, (2010) 859.

[23] P.B.Clapham, M.C.Hutley, Nature **244**, (1973) 281.

[24] D.J.Arrowsmith, Trans. Inst. Met. Finish. **48**, (1970) 88.

[25] K.X. Wang, Z. Yu, V. Liu, Y. Cui, S. Fan, Nano Lett. **12**, (2012) 1616.

[26] N.B. Abu Talip[a]Yusof, J. Taniguchi, Jpn. J. Appl. Phys. **53**, (2014) 06JK03.

[27] F.L. Gonzalez, M.J. Gordon, Opt. Express **22**, (2014) 12808.

[28] Z. Chen, Y. Gao, **53**, (2014) 3673.

[29] J.Y.Y.Loh, D.P.Puzzo, P.G. O'Brien, G. A. Ozin, N.P. Kherani, RSC Adv. **4**, (2014) 31188.

[30] K.-H. Tsui, Q. Lin, H. Chou, Q. Zhang, H. Fu, P. Qi, Z. Fan, Adv. Mater. **26**, (2014) 2805.

[31] Y. Li, F. Li, J. Zhang, C. Wang, S. Zhu, H. Yu, Z. Wang, B. Yang, Appl. Phys. Lett. 96, **43**, (2010) 255101.

[32] Y.-H. Ho, H. Liang, S.-W. Liu, W.-C. Tian, F.-C. Chen, P.-K. Wei, RSC Adv. **4**, (2014) 9588.

[33] P. Gao, M. Gu, X.L. Liu, B. Liu, S.M. Huang, Appl. Phys. Lett. **95**, (2009) 2013.

[34] Z. Zhu, B. Liu, C. Cheng, H. Chen, M. Gu, Y. Yi, R. Mao, Phys. Status Solidi **211**, (2014) 1583.

[35] X. Li, L. Xue, Y. Han, J. Mater. Chem. **21**, (2011) 5817.

[36] J. Cai, J. Ye, S. Chen, X. Zhao, D. Zhang, S. Chen, Y. Ma, S. Jin, L. Qi, Energy Environ. Sci. **5**, (2012) 7575.

[37] S. Ravipati, J. Shieh, F.-H. Ko, C.-C. Yu, H.-L. Chen, C.-T. Wu, S.-H. Chen, Energy Environ. Sci. **5**, (2012) 7601.

[38] M. Bender, M. Otto, B. Hadam, B. Spangenberg, H. Kurz, Microelectron. Eng. **61**, (2002) 407.

[39] S. Ahn, J. Cha, H. Myung, S.M. Kim, S. Kang, Appl. Phys. Lett. **89**, (2006) 9.

[40] S.H. Ahn, L.J. Guo, Adv. Mater. **20**, (2008) 2044.

[41] S.H. Ahn, L.J. Guo, ACS Nano **3**, (2009) 2304.

[42] M. Moro, J. Taniguchi, S. Hiwasa, J. Vac. Sci. Technol. B, Nanotechnol. Microelectron. Mater. Process. Meas. Phenom. **32**, (2014) 06FG09.

[43] J. Taniguchi, T. Kawasaki, Y. Tokano, Y. Kogo, I. Miyamoto, M. Komuro, H. Hiroshima, N. Sakai, K. Tada, Jpn. J. Appl. Phys. **41**, (2002) 4194.

[44] S. Garidel, M. Zelsmann, N. Chaix, P. Voisin, J. Boussey, A. Beaurain, B. Pelissier, J. Vac. Sci. Technol. B Microelectron. Nanom. Struct. **25**, (2007) 2430.

[45] F. A. Houle, C.T. Rettner, D.C. Miller, R. Sooriyakumaran, Appl. Phys. Lett. **90**, (2007) 213103.

[46] F. A. Houle, E. Guyer, D.C. Miller, R. Dauskardt, J. Vac. Sci. Technol. B Microelectron. Nanom. Struct. **25**, (2007) 1179.

[47] D. Yamashita, J. Taniguchi, H. Suzuki, Microelectron. Eng. **97**, (2012) 109.

[48] K. Yajima, K. Adachi, Y. Tsukahara, J. Taniguchi, Microelectron. Eng. **110**, (2013) 188.

[49] K.D. Kim, H.J. Kwon, D.G. Choi, J.H. Jeong, E.S. Lee, Jpn. J. Appl. Phys. **47**, (2008) 8648.

[50] M. Im, H. Im, J.-H. Lee, J.-B. Yoon, Y.-K. Choi, Soft Matter **6**, (2010) 1401.

[51] P. Glaris, J.F. Coulon, M. Dorget, F. Poncin-Epaillard, Compos. Part B Eng. **73**, (2015) 10.

[52] N. Nakamura, T. Yamashita, T. Kitagawa, H. Kawata, M. Shirai, Y. Hirai, J. Photopolym. Sci. Technol. **27**, (2014) 111.

[53] K. Wu, X. Wang, E.K. Kim, C.G. Willson, J.G. Ekerdt, Langmuir **23**, (2007) 1166.

[54] Y. Otsuka, S. Hiwasa, J. Taniguchi, Microelectron. Eng. **123**, (2014) 192.

[55] K. Sogo, M. Nakajima, Y. Hirai, J. Photopolym. Sci. technol. **19**, (2006) 647.

[56] T. Yanagishita, T. Kondo, K. Nishio, H. Masuda, J. Vac. Sci. Technol. B Microelectron. Nanom. Struct. **26**, (2008) 1856.

LIST OF PUBLICATIONS

A. Accepted/Published papers

1. N. B. Abu Talip[a]Yusof, T. Hayashi, J. Taniguchi, and S. Hiwasa, "Lifetime prolongation of release agent on antireflection structure molds by means of partial-filling ultraviolet nanoimprint lithography." 2015 International Conference on Electronic Packaging and iMAPS All Asia Conference (ICEP-IACC), IEEE pp. 418-421 (2015).
2. N. B. Abu Talip[a]Yusof, T. Hayashi, J. Taniguchi, and S. Hiwasa, "Lifetime amelioration of release-agent-free antireflection-structured replica molds by partial-filling ultraviolet nanoimprint lithography", Jpn. J. Appl. Physc. **54**, (2015) 06FM04.
3. N. B. Abu Talip[a]Yusof, T. Hayashi, J. Taniguchi, and S. Hiwasa, "Lifetime amelioration of antireflection structure molds by means of partial-filling ultraviolet nanoimprint lithography", Microelectron. Eng. **141**, (2015) 81.
4. N. B. Abu Talip[a]Yusof and J. Taniguchi, "Fabrication of double-sided self-supporting antireflection-structured film by ultraviolet nanoimprint lithography", Jpn. J. Appl. Physc. **53**, (2014) 06JK03.
5. N. B. Abu Talip[a]Yusof and J. Taniguchi, "Fabrication of self-supporting antireflection-structured film by UV-NIL", Microelectron. Eng. **110**, (2013) 163.

B. Conference oral presentation

1. N. B. Abu Talip[a]Yusof, T. Hayashi, J. Taniguchi, and S. Hiwasa, "Lifetime prolongation of release agent on antireflection structure molds by means of partial-filling ultraviolet nanoimprint lithography", 2015 International Conference on Electronic Packaging & iMAPS All Asia Conference, Kyoto Terrsa, Kyoto, Japan. (14/04/2015-17/04/2015)

C. Conference poster presentation

1. N. B. Abu Talip[a]Yusof, T. Hayashi, J. Taniguchi, and S. Hiwasa, "Lifetime amelioration of release-agent-free antireflection-structured replica molds by partial-filling ultraviolet

nanoimprint lithography", 27th International Microprocesses and Nanotechnology Conference, Hilton Fukuoka Sea Hawk, Fukuoka, Japan. (04/11/2014-07/11/2014)

2. N. B. Abu Talip[a]Yusof, T. Hayashi, J. Taniguchi, and S. Hiwasa, "Lifetime amelioration of antireflection structure molds by means of partial-filling ultraviolet nanoimprint lithography", 40th International Conference on Micro and Nano Engineering, Lausanne, Switzerland. (22/09/2014-26/09/2014)
3. N. B. Abu Talip[a]Yusof and J. Taniguchi, "Fabrication of double-sided self-supporting antireflection-structured film by ultraviolet nanoimprint lithography", 26th International Microprocesses and Nanotechnology Conference, Royton Sapporo, Hokkaido, Japan. (05/11/2013-08/11/2013)
4. N. B. Abu Talip[a]Yusof and J. Taniguchi, "Fabrication of self-supporting antireflection-structured film by UV-NIL", 38th International Conference on Micro and Nano Engineering, Toulouse, France. (16/09/2012-20/09/2012)